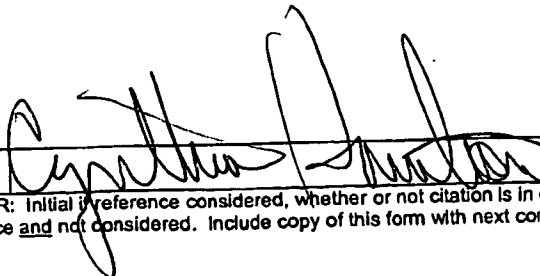


FIRST INFORMATION DISCLOSURE STATEMENT BY APPLICANT <small>(use as many sheets as necessary)</small>			Complete if Known		
			Application Number	10/764,407	
			Filing Date	January 23, 2004	
			First Named Inventor	Shenggao Liu et al.	
			Examiner Name		
Sheet	3	of	3	Attorney Docket Number	005950-844

FOREIGN PATENT DOCUMENTS											
Examiner Initials	Document Number	Kind Code (if known)	Country	Date of Publication (MM-DD-YYYY)	STATUS						
					Translation	Partial Translation	Eng. Lang. Summary	Search Report	IPER	Abstract	Cited In Spec
GH CH CH	WO 92/13909		PCT	08/20/92							
	WO 02/058139		PCT	07/25/02							
	WO 02/088077		PCT	11/07/02							

NON-PATENT LITERATURE DOCUMENTS	
Examiner Initials	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.
GH	LIAW, Der-Jang, "Synthesis and characterization of new polyamides and polyimides prepared from 2,2-bis[4-(4-aminophenoxy)phenyl]adamantane," <i>Macromol. Chem. Phys.</i> 200. No. 6, pp. 1326-1332 (1999)
GH	NOZAKI, Koji et al., "High-Performance Resist Materials for ArF Excimer Laser and Electron Beam Lithography," <i>FUJITSU Sci Tech. J.</i> , 38, 1, pp. 3-12 (June 2002)
GH	PADMANABAN, Munirathna, et al., "Etch Properties of 193nm Resists: Issues and Approaches," <i>Journal of Photopolymer Science and Technology</i> , Vol 15, No. 3 (2002), pp. 521-528
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GH	PANIEZ, P. J., et al., "Thermal Phenomena in Acrylic 193 nm Resists," <i>SPIE Conferences on Advances in Resist Technology and Processing XVI</i> , Santa Clara, CA, <i>SPIE</i> Vol. 3678 pp. 1352-1363 JUNE 1999 /CH/ 10/1/08
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Examiner Signature		Date Considered	9/9/05
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*EXAMINER: Initial reference considered, whether or not citation is in conformance with M.P.E.P. § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.